§12. Development of Deuterium Negative Ion Sources and Its Database Construction

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In a tandem volume source, H ions are generated by the dissociative attachment of slow plasma electrons $e_s(T_e - 1eV)$ to highly vibrationally excited hydrogen molecules $H_2(v^{"})$ (effective vibrational level $v^{"} \ge 5-6$). These $H_2(v^{"})$ are mainly produced by collisional excitation of fast electrons e_f with optimum energy of about 40 eV. Namely, H⁻ ions are produced by the following two step process, i.e. $H_2(v^{"})$ production and H⁻ formation:

$H_2(X^1 \Sigma g, v'' = 0) + e_f \rightarrow H_2^*(B^1 \Sigma u, C^1 \Sigma u) + e_f'$	(la)
$\mathrm{H}_{2}^{*}(\mathrm{B}^{1}\Sigma \mathrm{u}, \mathrm{C}^{1}\Sigma \mathrm{u}) \rightarrow \mathrm{H}_{2}(\mathrm{X}^{1}\Sigma \mathrm{g}, \mathrm{v}^{\prime\prime}) + \mathrm{h} \nu$	(lb)
$\mathbf{U}(w^{n}) \vdash \mathbf{a} \longrightarrow \mathbf{U}^{n} \vdash \mathbf{U}$	(2)

$$\Pi_2(\mathbf{v}) + \mathbf{c}_S = \mathbf{i} + \mathbf{i} + \mathbf{i}$$

Production process of D^{-} ions is believed to be the same as that of H⁻ ions described above. We have studied relationship between negative ion (i.e. H⁻ and D⁻ ions) productions ^{1, 2,3)} and plasma parameters across the magnetic filter (MF).



Fig. 1. Schematic diagram of the ion source.

Figure 1 shows a schematic diagram of a rectangular ion source. The arc chamber (plasma generator) is 25×25 cm in cross-section and 19 cm in height. By varying the intensity of the MF, axial distributions of T_e and n_e in both H₂ and D₂ plasmas are changed strongly in the downstream region^{2.3)}. Both patterns of T_e and n_e distributions are strongly dependent

on the MF intensity.

D density distributions are compared to H density distributions in the same discharge conditions. Figure 2 shows axial distributions of photodetached electron signals and obtained negative ion densities, where $B_{MF} = 80$ G, $p(H_2) = p(D_2) = 1.5$ mTorr, respectively. Axial distribution of D density is lower than that of H density. From viewpoint of plasma production, T_e in D_2 plasma is higher than that in H_2 plasma.





Variation of H⁻ and D⁻ production due to changes in plasma parameter distributions across the MF are discussed by taking into account main collision processes for production and destruction, i.e. dissociative attachment (DA: $H_2(v^{"})+e \rightarrow H^-$ + H) process and collisional electron detachment (ED: H⁺ + e \rightarrow H + 2e) process. Influence of D⁻ destruction by ED process on D⁻ density is higher than that of H⁻ distribution although n_e in D₂ plasma is higher than n_e in H₂ plasmas. Extracted D⁻ current is also lower than H⁻ current, and the ratio of H⁻ to D⁻ current is almost the same as the ratio of H⁻ to D⁻ density in front of the extraction hole. Therefore, extracted D⁻ current is mainly determined by D⁻ density in front of the extraction hole.

It is reconfirmed ^{2,3)} that T_e in the extraction region should be reduced below 1 eV with keeping n_e higher by using the MF, including good combination of filament position and the MF with a certain intensity. Control of not only T_e but also n_e in the extraction region is very important for enhancement of H and D production.

References

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